

INFORMATION DISCLOSURE CITATION IN AN APPLICATION (PTO-1449) 			ATTY. DOCKET NO. 008066 USA/ MTCG/PCTRL	SERIAL NO. 10/809,908		
			APPLICANT Susie Xiuru YANG et al.			
			FILING DATE March 26, 2004	GROUP 2812		
U.S. PATENT DOCUMENTS						
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)						
BQ	Boning, Duane et al. "Run by Run Control of Chemical-Mechanical Polishing." <i>IEEE Trans.</i> October 1996. Vol. 19, No. 4. pp. 307-314.					
BQ	Moyné, James et al. "A Run-to-Run Control Framework for VLSI Manufacturing." <i>Microelectronic Processing '93 Conference Proceedings.</i> September 1993.					
BQ	Telfeyan, Roland et al. "Demonstration of a Process-Independent Run-to-Run Controller." <i>187th Meeting of the Electrochemical Society.</i> May 1995.					
BQ	Moyné, James et al. "A Process-Independent Run-to-Run Controller and Its Application to Chemical-Mechanical Planarization." <i>SEMI/IEEE Adv. Semiconductor Manufacturing Conference.</i> August 15, 1995.					
BQ	Moyné, James et al. "Adaptive Extensions to be a Multi-Branch Run-to-Run Controller for Plasma Etching." <i>Journal of Vacuum Science and Technology.</i> 1995.					
BQ	Sachs, Emanuel et al. "Process Control System for VLSI Fabrication."					
BQ	Chaudhry, Nauman et al. "Active Controller: Utilizing Active Databases for Implementing Multi-Step Control of Semiconductor Manufacturing." <i>University of Michigan.</i> pp. 1 - 24.					
BQ	Chaudhry, Nauman et al. "Designing Databases with Fuzzy Data and Rules for Application to Discrete Control." <i>University of Michigan.</i> pp. 1 - 21.					
BQ	Chaudhry, Nauman A. et al. "A Design Methodology for Databases with Uncertain Data." <i>University of Michigan.</i> pp. 1 - 14.					
BQ	Khan, Kareemullah et al. "Run-to-Run Control of ITO Deposition Process." <i>University of Michigan.</i> pp. 1 - 6.					
BQ	Moyné, James et al. "Yield Improvement @ Contact Through Run-to-Run Control."					
BQ	Kim, Jiyoun et al. "Gradient and Radial Uniformity Control of a CMP Process Utilizing a Pre- and Post-Measurement Strategy." <i>University of Michigan.</i>					
EXAMINER 	DATE CONSIDERED 11/14/05					

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.